## PRESS RELEASE

## The Ultimate Defense Against Hackers May Be Just a Few Atoms Thick

November 29, 2017

NYU Tandon Researchers Discover Big Cryptographic Potential in Nanomaterial



(a) At monolayer thickness, this material has the optical properties of a semiconductor that emits light. At multilayer, the properties change and the material doesn't emit li speckled with randomly occurring regions that alternately emit or block light. (c) Upon exposure to light, this pattern can be translated into a one-of-a-kind authentication

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hand as researchers at New York University Tandon School of Engineering introduce а new class of unclonable cybersecurity security primitives made of а lowcost nanomaterial with the highest possible level of structural randomness. Randomness is highly desirable for constructing the security primitives that encrypt and thereby secure computer la a .. al. . . a .. a

and data physically, rather than by programming. In а paper published in the journal ACS Nano, Assistant Professor of Electrical and Computer Engineering Davood <u>Shahrjerdi</u> and his NYU Tandon team offer the first proof of complete spatial randomness in atomically thin molybdenum disulfide (MoS2). The researchers grew the nanomaterial

layers, each roughly one million times thinner than а human hair. Ву varying the thickness of each layer, Shahrjerdi explained, they tuned the size and type of energy band structure, which in turn affects the properties of the material. "At monolayer thickness, this material has the optical properties of

semiconductor that emits light, but at multilayer, the properties change, and the material no longer emits light. This property is unique to this material," he said. Ву tuning the material growth process, the resulting thin film is speckled with randomly occurring regions that alternately emit or do not emit الم ما به ا

When exposed to light, this pattern translates into а oneofakind authentication key that could secure hardware components at minimal cost. Shahrjerdi said his team was pondering potential applications for what he described as the beautiful random light patterns of MoS2 when he realized it would be

valuable as а cryptographic primitive. This represents the first physically unclonable security primitive created using this nanomaterial. Typically embedded in integrated circuits, physically unclonable security primitives protect or authenticate hardware or digital information. They interact with а stimulus \_ in this case, light \_ to produce а unique response + l= = +

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Shahrjerdi
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The
paper,
"Physically
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Layered
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appears
in
the
journal
ACS
Nano
at
http://pubs.acs.org/doi/10.1021/acsnano.7b07568.
Co-
authors
include
NYU
Tandon
doctoral
candidate
Abdullah
```

and
graduate
students
Darren
Armstrong
and
Somayah
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The
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